Electrical and thermal transport properties of CdO and CdMgO alloys grown using PA-MBE technique Jaszowieg School & Conference

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Introduction

- Oxide semiconductors are promising candidates for optoelectronic applications because of advantages like large bandgap energy, and high mechanical and chemical stability.
- CdO is one of the oldest known semiconductor oxides that have been studied widely because of its high electron concentration, high transparency, high electron mobility, low resistivity, and high exciton binding energy.
- Development of advanced growth techniques and in situ characterization methods allowed not only to grow high-quality CdO layers but also related ternary alloys (such as ZnCdO and CdMgO) which in turn can be used in many wide spectral range applications.
- Plasma-assisted molecular beam epitaxy (PA-MBE) allows the most precise control of growth parameters, such as growth rate, and flux of Cd, which could be monitored by a variety of in situ characterization techniques such as flux monitor, laser reflectometry, and desorption mass spectroscopy.
- In this work, we have investigated a series of CdO and CdMgO layers grown on m-plane sapphire and quartz substrate using PA-MBE technique.



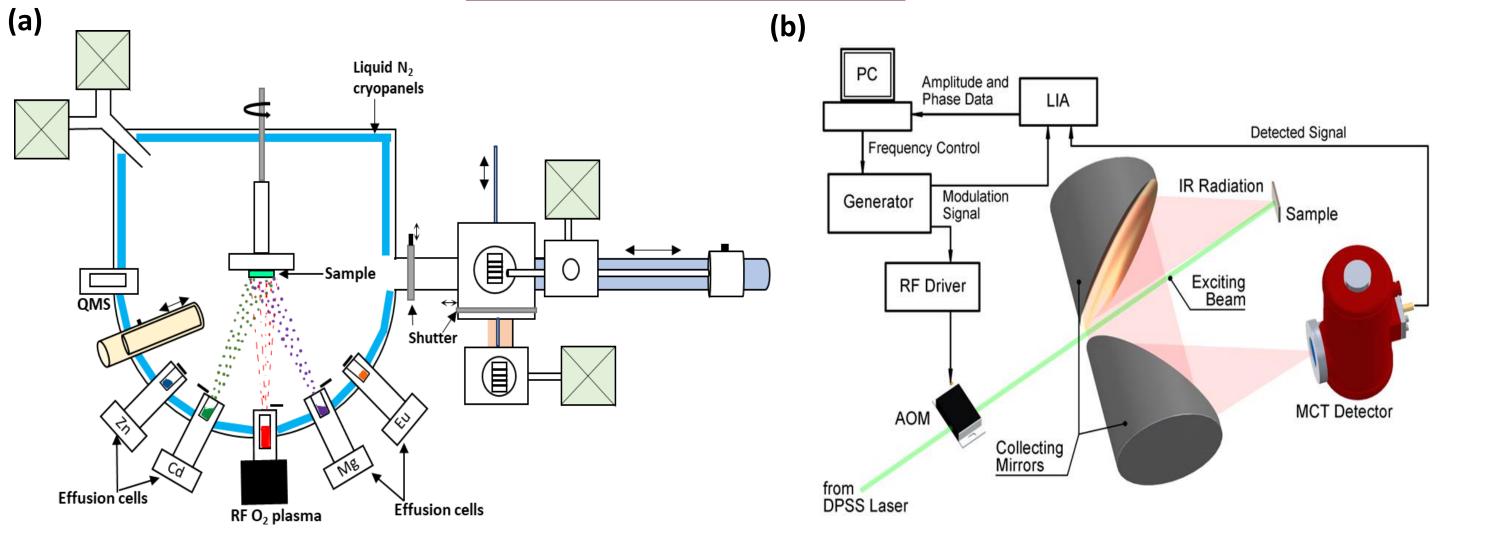
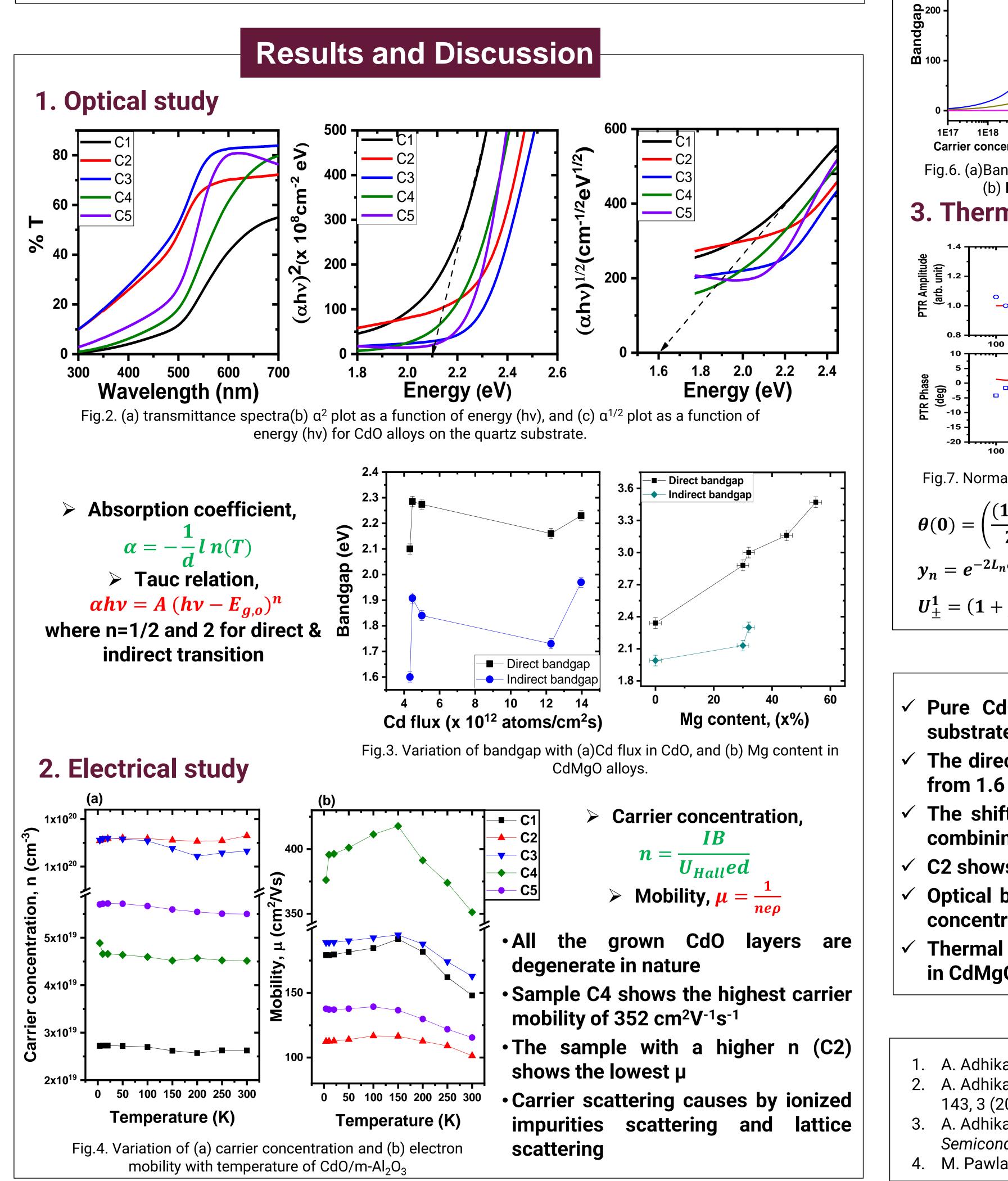
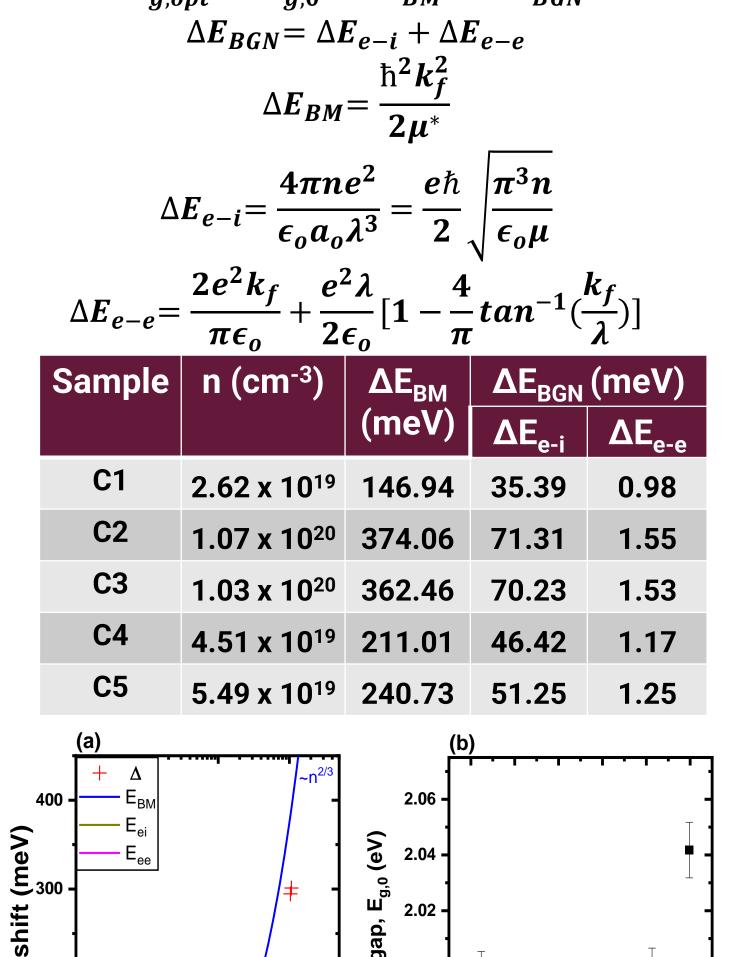
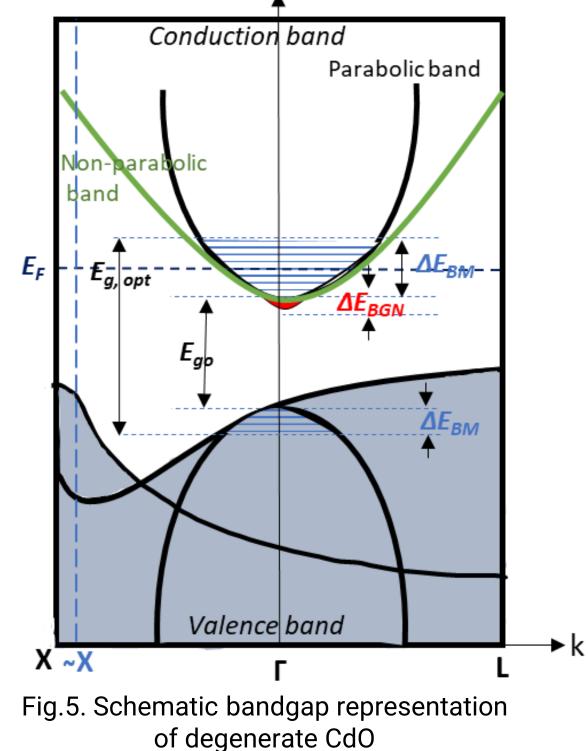


Fig.1. Schematic representation of (a) oxide MBE setup (b) photothermal radiometry setup

- CdO and CdMgO random alloys were grown using plasma-assisted MBE technique (PA-MBE) on *m*- plane sapphire and quartz substrates respectively
- The following characterization were performed:
 - \Box Optical study \rightarrow UV-Vis spectroscopy
 - \Box Electrical study \rightarrow Hall measurement
 - \Box Thermal study \rightarrow Photothermal infrared radiometry







 In degenerate CdO layers, electron occupation in the CBM and VBM causes bandgap widening

 Random distributions of impurities cause electron-ion interaction whereas the electron-electron interaction is due to Columbic charge carriers in the semiconductor band

• ΔE_{e-e} values are much lower compared

to ΔE_{e-i}

Carrier concentration, n (cm⁻³) Cd flux (x 10¹² atoms/cm²s) Fig.6. (a)Bandgap shift as a function of carrier concentration (b) Intrinsic bandgap with change in Cd flux

2.00

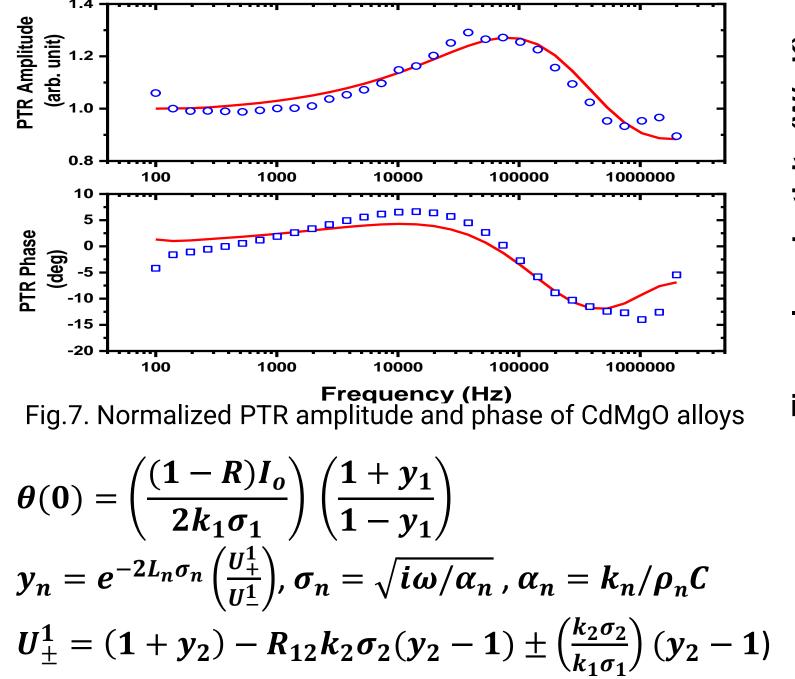
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4 6 8 10 12 14

3. Thermal study

1E19

1E20



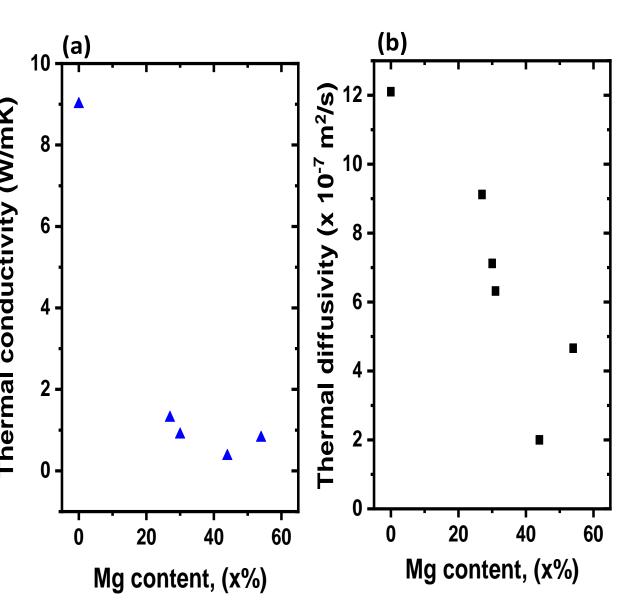


Fig.8. Variation of (a)thermal conductivity and (b)thermal diffusivity with change in Mg content in CdMgO alloys

Conclusions

- Pure CdO layer and CdMgO layers were grown on m-plane sapphire and quartz substrate using PA-MBE technique.
- The direct bandgap varies from 2.1 eV to 2.33 eV whereas the indirect bandgap varies from 1.6 eV to 1.97 eV for pure CdO layers with a change in Cd flux
- \checkmark The shifting of bandgap toward higher energies depends upon n and is acquired by combining the effect of bandgap widening (BGW) and bandgap narrowing (BGN) effects.
- C2 shows maximum n of 1.06 x 10^{20} cm⁻³ and C6 shows maximum μ of 352 cm²V⁻¹s⁻¹
- Optical bandgap (both direct and Indirect bandgap) increases with an increase in Mg concentration in CdMgO alloys.
- Thermal conductivity and diffusivity decreases with increases in Mg content up to 50% in CdMgO alloys and started to increase above 50 %, as expected for bulk crystal.

References

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This work was supported in part by the Polish National Science Center, Grants No. 2021/41/N/ST5/00812, and 2021/41/B/ST5/00216.

